## **Claims**

5

10

20

- 1. A capacitor dielectric comprising a material formed from a two-component plasma reaction in a substantially air-evacuated plasma chamber, a first component of the two-component plasma reaction comprising a non-carbon containing and non-oxygenated silicon donor, and a second component of the two-component plasma reaction comprising a non-silicon containing and non-oxygenated organic precursor.
- 2. The capacitor dielectric of claim 1 wherein the second component of the two-component plasma reaction is selected from the group consisting of alkanes, alkenes, alkynes, phenyls and aromatic hydrocarbons.
  - 3. The capacitor dielectric of claim 1 wherein the second component of the two-component plasma reaction is selected from the group consisting of ethylene, methane, ethane and toluene.
  - 4. The capacitor dielectric of claim 1 wherein the first component of the two-component plasma reaction is selected from the group consisting of monosilane, disilane and dichlorsilane.
  - 5. The capacitor dielectric of claim 4 wherein the second component of the two-component plasma reaction is selected from the group consisting of ethylene, methane, ethane and toluene.
- 25 6. The capacitor dielectric of claim 1 wherein the capacitor dielectric is photo-oxidized by exposure to a radiated electromagnetic energy in the presence of oxygen to alter the dielectric constant of the capacitor dielectric subsequent to the formation of the capacitor dielectric.

15

5

## 7. A capacitor comprising:

a first conductor;

a dielectric formed on the first conductor from a two-component plasma reaction in a substantially air-evacuated plasma chamber, a first component of the two-component plasma reaction comprising a non-carbon containing and non-oxygenated silicon donor, and a second component of the two-component plasma reaction comprising a non-silicon containing and non-oxygenated organic precursor; and

a second conductor formed on the dielectric.

- 8. The capacitor of claim 7 wherein the second component of the two-component plasma reaction is selected from the group consisting of alkanes, alkenes, alkynes, phenyls and aromatic hydrocarbons.
  - 9. The capacitor of claim 7 wherein the second component of the two-component plasma reaction is selected from the group consisting of ethylene, methane, ethane and toluene.
  - 10. The capacitor of claim 7 wherein the first component of the two-component plasma reaction is selected from the group consisting of monosilane disilane and dichlorsilane.
  - 20 11. The capacitor of claim **10** wherein the second component of the two-component plasma reaction is selected from the group consisting of ethylene, methane, ethane and toluene.
    - 12. The capacitor of claim 7 wherein the dielectric is photo-oxidized by exposure to a radiated electromagnetic energy in the presence of oxygen to alter the dielectric constant of the dielectric subsequent to the formation of the dielectric.
    - 13. The capacitor of claim 7 wherein the dielectric is photo-oxidized by exposure to a radiated electromagnetic energy in the presence of oxygen to alter the dielectric constant of the dielectric when the capacitor is in an electrically active circuit.

25

15

20

25

5

## 14. An electrical filter comprising:

a one or more capacitors, an at least one of the one or more capacitors comprising:

a first conductor:

a dielectric formed on the first conductor from a two-component plasma reaction in a substantially air-evacuated plasma chamber, a first component of the two-component plasma reaction comprising a non-carbon containing and non-oxygenated silicon donor, and a second component of the two-component plasma reaction comprising a non-silicon containing and non-oxygenated organic precursor; and

a second conductor formed on the dielectric; and

a one or more inductors electrically connected to the one or more capacitors to form an electrical filter.

- 15. The electrical filter of claim 14 wherein an at least one of the one or more inductors comprises an on-chip spiral inductor.
- 16. A method of fabricating a capacitor dielectric comprising the step of forming the capacitor dielectric from a two-component plasma reaction in a substantially air-evacuated plasma chamber, a first component of the two-component plasma reaction comprising a non-carbon containing and non-oxygenated silicon donor, and a second component of the two-component plasma reaction comprising a non-silicon containing and non-oxygenated organic precursor.
- 17. The method of claim 16 further comprising the step of photo-oxidizing the capacitor dielectric by exposing the capacitor dielectric to radiated electromagnetic energy in the presence of oxygen subsequent to the two-component plasma reaction.
- 18. The method of claim 16 wherein the second component of the two-component plasma reaction is selected from the group consisting of alkanes, alkenes, alkynes, phenyls and aromatic hydrocarbons.

- 19. The capacitor of claim **16** wherein the second component of the two-component plasma reaction is selected from the group consisting of ethylene, methane, ethane and toluene.
- The capacitor of claim 16 wherein the first component of the two-component plasma
  reaction is selected from the group consisting of monosilane disilane and dichlorsilane.